



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Rex K. Frost et al.                      Art Unit:  
Serial No.: 10/698,782                                  Examiner:  
Filed : October 31, 2003  
Assignee : Intel Corporation  
Title : ACCOMMODATING DIFFRACTION IN THE PRINTING OF  
              FEATURES ON A SUBSTRATE

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Applicants call attention to the attached Information  
Disclosure Statement and documents listed on form PTO-1449.

This filing is being made before the receipt of a first  
Office action on the merits. No fee is required.

The documents are in the English language; hence no concise  
explanation is necessary per Rule 98(a)(3).

Consideration of the foregoing and enclosures plus the  
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Applicant : Rex K. Frost et al.  
Serial No.: 10/698,782  
Filed : October 31, 2003

Attorney's Docket No.:10559-863001

Examiner's initials in the left column per MPEP 609 are  
earnestly solicited along with an early action on the merits.

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Respectfully submitted,



John F. Conner, Reg # 45,485  
for

Date: \_\_\_\_\_

2/27/04

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Substitute Form PTO-1449 (Modified) <b>Information Disclosure Statement</b> by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-863001	Application No. 10/698,782
	Applicant Rex K. Frost et al.		
	Filing Date October 31, 2003	Group Art Unit	

### U.S. Patent Documents

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA	6,492,069	12/2002	Wu, et al.			
	AB	6,500,587	12/2002	Ghandehari, et al.			
	AC	6,524,752	02/2003	Pierrat			
	AD	6,524,755	02/2003	Jin, et al.			
	AE	6,569,580	05/2003	Campi, et al.			
	AF						
	AG						

### Foreign Patent Documents or Published Foreign Patent Applications

Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AH							
	AI							

### Other Documents (include Author, Title, Date, and Place of Publication)

Examiner Initial	Desig. ID	Document
	AJ	Liebmann, L., "Layout Impact of Resolution Enhancement Techniques: Impediment or Opportunity", <i>International Symposium on Physical Design 2003</i> , Session 7, pp. 110-117, Monterey, CA, April 6-9 (2003).
	AK	Liebmann, L., "Resolution Enhancement Techniques in Optical Lithography, It's not just a Mask Problem", <i>Proceedings SPIE, Photomask and Next-Generation Lithography Mask Technology VIII</i> , Vol. 4409, pp. 23-32 (2001).
	AL	Nordquist, K., et al., "Critical Dimension and Image Placement Issues for Step and Flash Imprint Lithography Templates", <i>Proceedings of SPIE, 22nd Annual BACUS Symposium on Photomask Technology</i> , Vol. 4889, No. 129, pp. 1143-1150 (2002).
	AM	Petersen, J., et al., "Development of a Sub-100nm Integrated Imaging System Using Chromeless Phase-Shifting Imaging with Very High NA KrF Exposure and Off-axis Illumination", <i>Proceedings SPIE, Design, Process Integration, and Characterization for Microelectronics</i> , Vol. 4692, pp. 298-311 (2002).
	AN	Scheid, G., et al., "Contact Holes: Optical Area Measurement Predicts Printability and is Highly Repeatable", presented at Photomask Japan 2001, Paper 4409-11, pp. 1-6 (2001).
	AO	Zhang, H., et al., "Compact Formulation of Mask Error Factor for Critical Dimension Control in Optical Lithography", <i>Proceedings SPIE, Metrology, Inspection, and Process Control for Microlithography XVI</i> , Vol. 4689, pp. 462-465 (2002).
	AP	

Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	